L	Hits	S Search Text	- DR	mi
Number		Search lext	DB	Time stamp
7	16		USPAT;	2003/07/15
		electroplat\$3 same electropolish\$3 or	US-PGPUB;	11:37
1		(electrolytlic adj polish\$3)) and conveyor	EPO; JPO;	
1	612		DERWENT USPAT;	2003/07/15
		electroplat\$3 same electropolish\$3 or	US-PGPUB;	12:01
		(electrolytlic adj polish\$3)	EPO; JPO;	12.01
1,2			DERWENT	1
13	91		USPAT;	2003/07/15
1		electroplat\$3 same electropolish\$3 or (electrolytlic adj polish\$3)) and	US-PGPUB;	12:10
		204/\$.ccls.	EPO; JPO; DERWENT	
19	51		USPAT;	2003/07/15
			US-PGPUB;	12:16
			EPO; JPO;	
25	1	appeal 62 CAME	DERWENT	
23	1	anneal\$3 SAME copper adj electroplat\$3 AND electropolish\$3	USPAT;	2003/07/15
		The creeroportshys	US-PGPUB; EPO; JPO;	12:19
			DERWENT	
31	171966	anneal\$3	USPAT;	2003/07/15
			US-PGPUB;	12:19
			EPO; JPO;	
37	31602	chemical near5 polish\$3	DERWENT	0000/05/45
		onemical nears portshys	USPAT; US-PGPUB;	2003/07/15
1			EPO; JPO;	12.20
1.5			DERWENT	
43	6470	anneal\$3 AND (chemical near5 polish\$3)	USPAT;	2003/07/15
			US-PGPUB;	12:21
			EPO; JPO; DERWENT	
49	4081	electroplat\$3 NEAR copper	USPAT;	2003/07/15
	i		US-PGPUB;	12:22
			EPO; JPO;	
55	219	(anneal\$3 AND (chemical near5	DERWENT	
	213	polish\$3)) AND (electroplat\$3 NEAR	USPAT; US-PGPUB;	2003/07/15
		copper)	EPO; JPO;	12:25
			DERWENT	
61	3	I () I LED (CITCHITCHI IICHI)	USPAT;	2003/07/15
1	İ	polish\$3)) AND (electroplat\$3 NEAR	US-PGPUB;	12:25
	1	copper)) AND conveyor	EPO; JPO;	
67	0	((anneal\$3 AND (chemical near5	DERWENT USPAT;	2002/07/15
		polish\$3)) AND (electroplat\$3 NEAR	US-PGPUB;	2003/07/15 12:25
		copper)) AND conveyor AND chemical adj	EPO; JPO;	12.25
73	4	polish\$3	DERWENT	
'	4	(anneal\$3 AND (chemical near5 polish\$3)) AND (electroplat\$3 NEAR	USPAT;	2003/07/15
1		copper) AND chemical adj polish\$3	US-PGPUB;	12:26
	1		EPO; JPO; DERWENT	
-	275	205/223.ccls.	USPAT;	2003/07/15
			US-PGPUB;	11:31
	, 1		EPO; JPO;	[
_	15	205/223.ccls. and interconnect	DERWENT	2002/05/22
] - 1	The Interconnect	USPAT; US-PGPUB;	2003/05/13 18:16
	[EPO; JPO;	10.10
_	1 , 1	205 (222	DERWENT	
_	14	205/223.ccls. and interconnect and etch\$3	USPAT;	2003/05/13
	[gramma and the contract of the	US-PGPUB;	18:16
	•	•	EPO; JPO; DERWENT	
-	222	anneal\$3 adj section	USPAT;	2003/07/11
			US-PGPUB;	15:46
		,	EPO; JPO;	
	<u> </u>		DERWENT	

-	0	anneal\$3 adj section SAME	USPAT;	2003/07/11
		electropolish\$3	US-PGPUB;	15:41
			EPO; JPO;	
1_	0	anneal\$3 adj section SAME chemical adj	DERWENT USPAT;	2003/07/11
		polish	US-PGPUB;	15:41
		Pollon	EPO; JPO;	15.41
			DERWENT	
_	1	anneal\$3 adj section SAME chemical adj	USPAT;	2003/07/11
		polish\$3	US-PGPUB;	15:41
		ļ	EPO; JPO;	
			DERWENT	
-	165	anneal\$3 adj area	USPAT;	2003/07/11
			US-PGPUB;	15:45
			EPO; JPO; DERWENT	
-	6	(anneal\$3 adj area) AND (anneal\$3 adj	USPAT;	2003/07/11
		section)	US-PGPUB;	15:43
			EPO; JPO;	
1			DERWENT	
-	1	(USPAT;	2003/07/11
1		polish\$3	US-PGPUB;	15:45
			EPO; JPO;]
1_	0	annualta adi avea cama allamana allamana	DERWENT	2002/07/21
-	0	anneal\$3 adj area SAME electropolish\$3	USPAT;	2003/07/11
			US-PGPUB; EPO; JPO;	15:46
			DERWENT	!
_	4637	anneal\$3 SAME polish\$3	USPAT;	2003/07/11
	1		US-PGPUB;	15:48
			EPO; JPO;	
İ			DERWENT	
-	1924	(anneal\$3 SAME polish\$3) and electro\$10	USPAT;	2003/07/11
			US-PGPUB;	15:48
			EPO; JPO;	
_	16	anneal\$3 SAME electropolish\$3 SAME	DERWENT USPAT;	2003/07/11
		chemical	US-PGPUB;	15:52
			EPO; JPO;	10.02
			DERWENT	
-	1956	anneal\$3 AND 204/\$.ccls.	USPAT;	2003/07/11
			US-PGPUB;	15:53
			EPO; JPO;	
l_ i	38	anneal\$3 AND 204/\$.ccls. AND	DERWENT	2003/07/11
] 30	electropolish\$3	USPAT; US-PGPUB;	2003/07/11
		Clostopolismys	EPO; JPO;	10.20
			DERWENT	
[-	55192	(anneal\$3 AND 204/\$.ccls. AND	USPAT;	2003/07/11
[electropolish\$3) AND copper NEAR plat\$3	US-PGPUB;	16:13
		or electroplat\$3	EPO; JPO;	
<u> </u>	25	/anneal63 AND 204/61 - 320	DERWENT	2002/07/24
ļ ⁻	45	(anneal\$3 AND 204/\$.ccls. AND electropolish\$3) AND copper	USPAT; US-PGPUB;	2003/07/11 16:13
]		arroaroborranda) www cobber	EPO; JPO;	10.13
			DERWENT	
~	786	anneal\$3 AND chemical NEAR polish\$3	USPAT;	2003/07/11
		<u>-</u>	US-PGPUB;	16:24
			EPO; JPO;	
_	ا ۾		DERWENT	2002/07/55
-	0	anneal\$3 AND electrohemical NEAR	USPAT;	2003/07/11
	1	polish\$3	US-PGPUB;	16:23
			EPO; JPO; DERWENT	
_	55203	(anneal\$3 AND chemical NEAR polish\$3)	USPAT;	2003/07/11
		and copper adj plat\$3 or electroplat\$3	US-PGPUB;	16:28
ĺ			EPO; JPO;	
			DERWENT	
-	23	(anneal\$3 AND chemical NEAR polish\$3)	USPAT;	2003/07/14
		and copper adj plat\$3	US-PGPUB;	10:13
			EPO; JPO;	
			DERWENT	

~	9	(anneal\$3 AND electrolytic NEAR	USPAT;	2003/07/14
		polish\$3) and copper adj plat\$3	US-PGPUB;	10:04
		-	EPO; JPO;	
			DERWENT	
-	4	(anneal\$3 AND chemical NEAR polish\$3)	USPAT;	2003/07/14
		and copper adj plat\$3 AND ((anneal\$3	US-PGPUB;	10:05
		AND electrolytic NEAR polish\$3) and	EPO; JPO;	
		copper adj plat\$3)	DERWENT]
-	20	(anneal\$3 AND electrolytic NEAR10	USPAT;	2003/07/14
		polish\$3) and copper adj plat\$3	US-PGPUB;	10:47
			EPO; JPO;	
			DERWENT	ł
-	11	((=====================================	USPAT;	2003/07/14
l		polish\$3) and copper adj plat\$3) AND	US-PGPUB;	10:48
		((anneal\$3 AND electrolytic NEAR10	EPO; JPO;	
		polish\$3) and copper adj plat\$3)	DERWENT	<u> </u>
-	185	(anneal\$3 AND chemical NEAR10	USPAT;	2003/07/14
		polish\$3) and copper adj plat\$3	US-PGPUB;	11:21
			EPO; JPO;	
L			DERWENT	